



UVAPRINT HPV

High intensity UV curing unit

System-Features

- compact powerful UV-dryer
- two power steps (1 kW and 2 kW)
- power control 50 % / 100 %
- power output up to 200 W/cm
- all standard and many special spectra available
- low substrate temperature

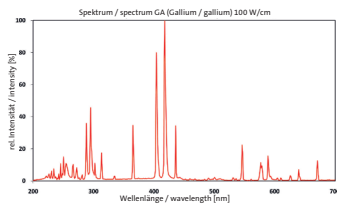
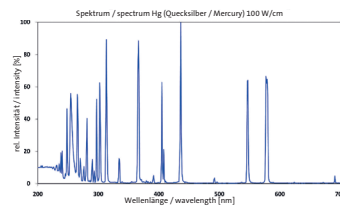
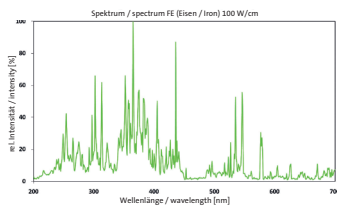
Advantages

- integration possible in almost all production processes
- highly efficient for the greatest production speeds
- service friendly due to modular design
- easy integration due to „Plug & Play“

High intensity UV curing unit

A compact high-intensity UV curing unit with CAD-designed reflector geometry guaranteeing **optimum UV yield**. Spectra and arc lengths are **easily adapted** for different applications **by just changing the lamp**. UVAPRINT HPV is used for curing UV reactive adhesives, compounds, plastics, inks and lacquers.

The **plug and play installation** is particularly easy. For both power steps 1 kW and 2 kW, the mains supply is 230 V, 50 Hz.



Standard spectra

Lamp unit

- high-performance UV lamp with arc lengths of 100, 150 or 200 mm
- CAD-optimised reflector geometry
- integrated fans in the lamp unit
- optional with electronically or pneumatically driven shutter or without shutter
- optional Advanced Cold Mirror system ACM for temperature reduction
- optional dichroic reflectors
- optional cooling plate

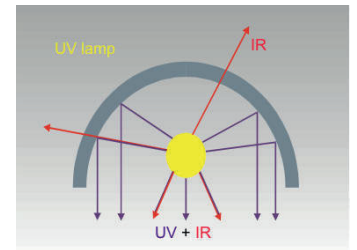
Control unit and power supply

- two-step power control 50 % / 100 % with an arc power output of:
 - 100 W/cm resp. 200 W/cm with an arc length of 100 mm
 - 66 W/cm resp. 133 W/cm with an arc length of 150 mm
 - 50 W/cm resp. 100 W/cm with an arc length of 200 mm
- interface for external shutter control and power steps 1 kW / 2 kW
- external „Lamp Error“ and „Shutter open/close“ signal
- optional remote control or remote control with timer
- dimensions (L x W x H): 400 x 250 x 634 mm

Optional reflectors

Dichroic reflectors

- reduction of IR radiation by approx. 40%
- reduction of temperature rise on the substrate by up to 30%
- retrofittable



Advanced Cold Mirror (ACM)

- IR-reduction by up to 85%
- reduction of temperature rise on the substrate by up to 65%
- retrofittable

